

REFLECTIVE MASK BLANK AND REFLECTIVE MASK

ABSTRACT

5

A reflective mask blank that is a material for a reflective mask used in EUV lithography using EUV light as exposure light, including a substrate, a multilayer reflection film that is formed on one main surface of the substrate and reflects the exposure light, and an absorber film containing tungsten, and another metal, a metalloid or a light element that
10 is formed on the multilayer reflection film and absorbs the exposure light.

[Figure 1]